

⌚ BRS: 32 with 33

⌚ Pending

⌚ Active

- ⌚ L1: (1) 10/718310
- ⌚ L2: (6) 5519236.pn. "20020127803" "20020127796"
- ⌚ L3: (1342) (semiconductor active) adj (strip\$4 web)
- ⌚ L4: (17333) second adj2 well
- ⌚ L5: (554) (257/302).CCCLS
- ⌚ L6: (10) 4 and 5
- ⌚ L7: (17854) first adj2 well
- ⌚ L8: (73343) "same" near 2 (conduct\$4 impurity dop\$4)
- ⌚ L9: (4658) 4 with 7
- ⌚ L10: (48) 9 with 8
- ⌚ L11: (45548) (wordline "WL" (word near (read\$3 writ\$3)))
- ⌚ L12: (3216814) contact
- ⌚ L13: (0) 10 with 11
- ⌚ L14: (5090) deep adj trench
- ⌚ L15: (715) buried adj strap
- ⌚ L16: (180) 14 near 8 15
- ⌚ L17: (3149775) identical similar \$2
- ⌚ L18: (5) (17 "same") with 16
- ⌚ L19: (1) 09/607217
- ⌚ L20: (20) 26 18

⌚ Failed

⌚ Saved

- ⌚ (1) 09/948877

• Failed
• Saved

Saved

1109948877

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DBs:	USPAT;US_PGPUB;EPO;JPO;DERVENT;IBM_TDB		
Default operator:	CR		
2018			
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#	Applicant	Document	Issue Date	Title	Current Status	Current IPR	Retrieved	S	C	P	Image	Doc. P
1	<input type="checkbox"/> <input checked="" type="checkbox"/>	Bostelmann, US 6344390	20020202	Methods of forming the buried strap and its g	438/249;257/E21.65	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 6344390	
2	<input type="checkbox"/>	Kowalski, Be	US 2004010 200409	Transistor array and semiconductor memory	257/302	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2004010	
3	<input type="checkbox"/> <input type="checkbox"/>	Lose, Beate	US 2002019 200211	Method for etching silicon trenches	438/709;257/302;	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2002019	
4	<input type="checkbox"/> <input type="checkbox"/>	Schlösser, Till	US 2002012 200201	Method for producing a memory cell for a se	438/258;257/E21.65	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2002012	
5	<input type="checkbox"/> <input type="checkbox"/>	Hofmann, Fra	US 2002012 200201	Method for producing a cell of a semiconduct	438/243;257/E21.65	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2002012	
6	<input type="checkbox"/> <input type="checkbox"/>	Kim, Ho-Hyun	US 2002008 200201	MOS control diode and method for manufac	257/135;257/242;	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2002008	
7	<input type="checkbox"/> <input type="checkbox"/>	Wu, Xiaojia et	US 2002007 200201	Electronic circuit with electrical hole isolat	257/302;257/E21.37	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2002007	
8	<input type="checkbox"/> <input type="checkbox"/>	Hsu, Louis L	US 2002007 200201	Structure and method for creating vertical c	257/302;257/E23.14	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 2002007	
9	<input type="checkbox"/> <input type="checkbox"/>	Schroeder, H	US 8747303 200401	CHARGE DETECTOR SEMICONDUCTOR CO	257/296;257/297;	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 8747303	
10	<input type="checkbox"/> <input type="checkbox"/>	Seitz, Mihel	US 6706634 200401	Control of separation between transfer gate	438/692;257/E21.65	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/> <input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	US 6706634	